

Positron Annihilation for Materials Science & The intense Positron Source EPOS



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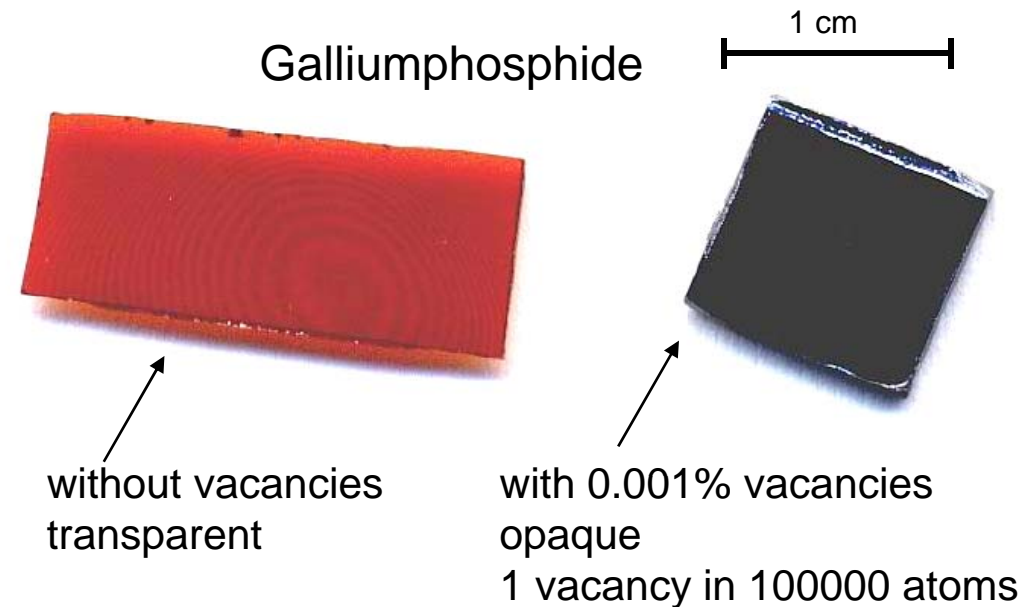
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- Why are nano-defects important at all?
- Positron trapping by defects
- Positronium to probe pores
- New positron facilities - the EPOS Project



Point defects determine properties of materials

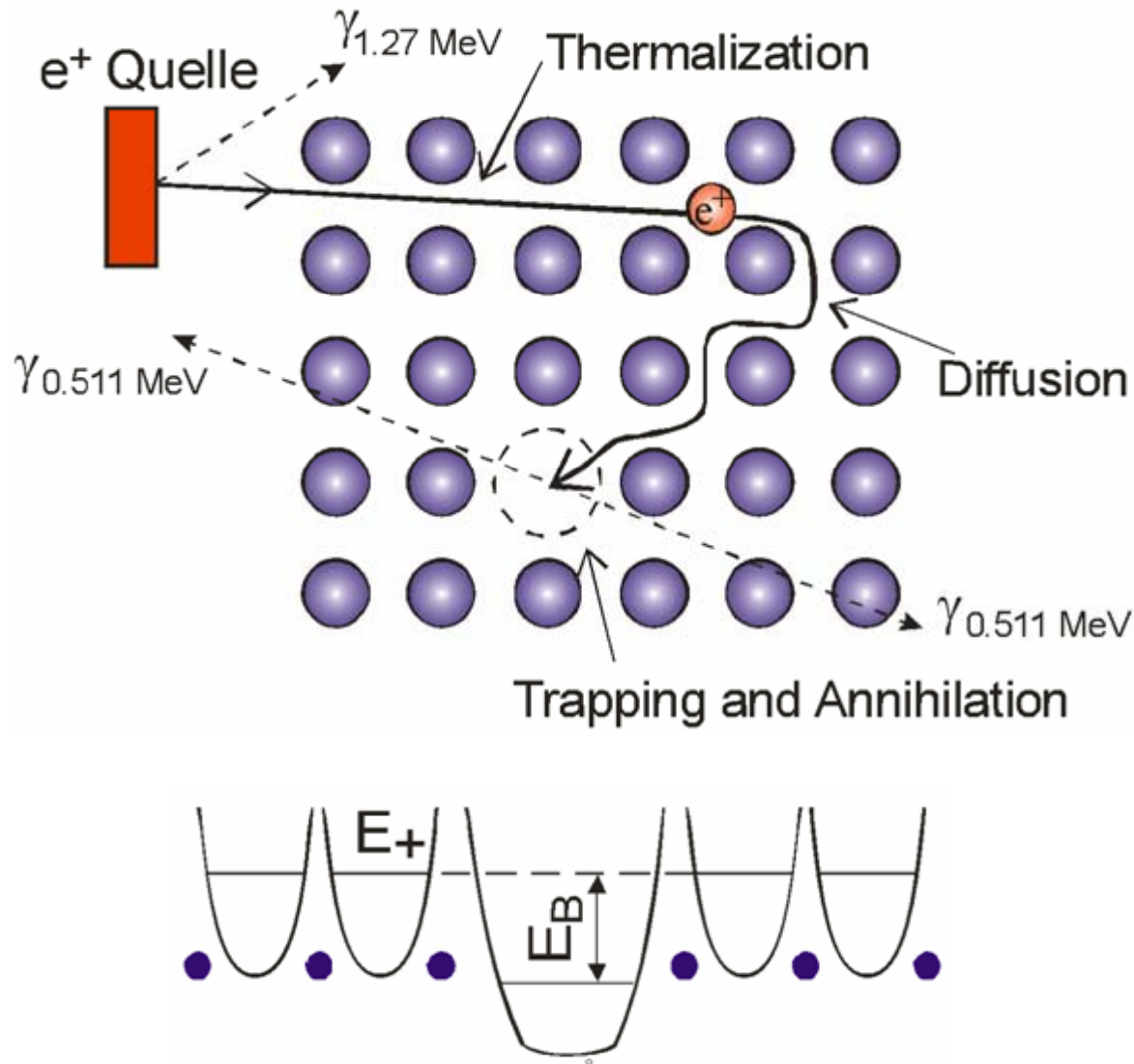
- Point defects determine electronic and optical properties
- electric conductivity strongly influenced
- Doping of semiconductors (n-, p-Si)



- Point defects are generated by irradiation (e.g. cosmic rays), by plastic deformation or by diffusion, ...
- Metals in high radiation environment -> formation of voids -> embrittlement
- -> Properties of vacancies and other point defects must be known
- Analytical tools are needed to characterize point defects

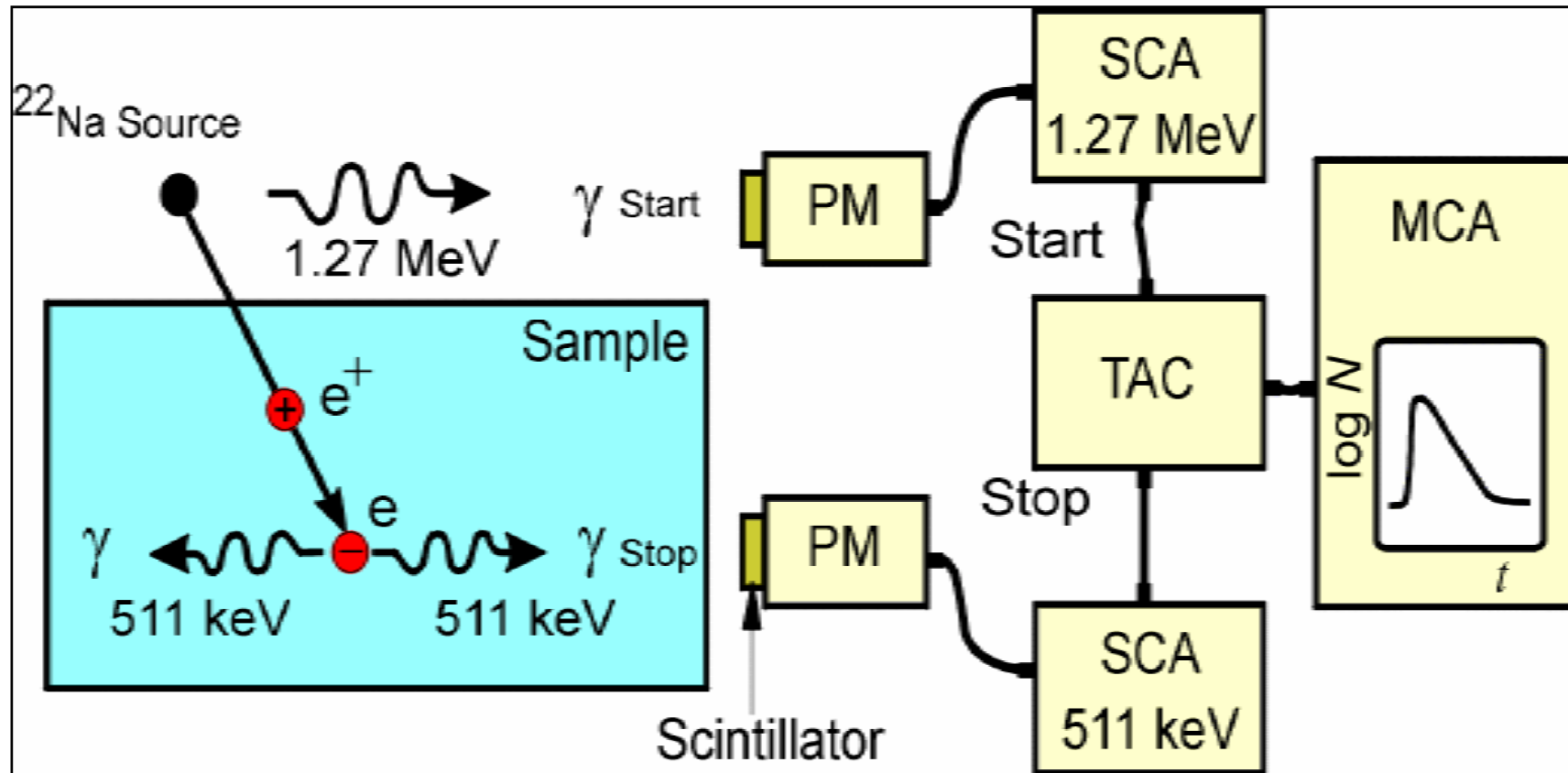
The positron lifetime spectroscopy

^{22}Na



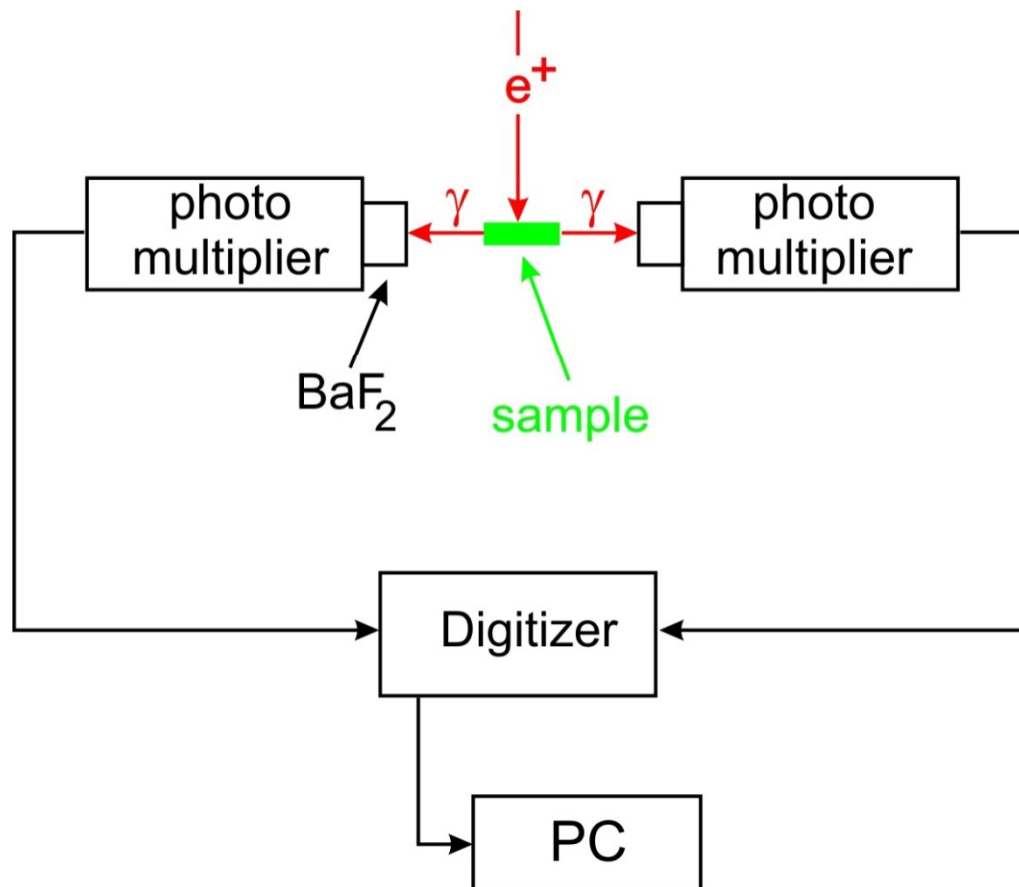
- positron wave-function can be localized in the attractive potential of a defect
- annihilation parameters change in the localized state
- e.g. positron lifetime increases in a vacancy
- lifetime is measured as time difference between appearance of 1.27 (start) and 0.51 MeV (stop) quanta
- defect identification and quantification possible

The positron lifetime spectroscopy - conventional setup



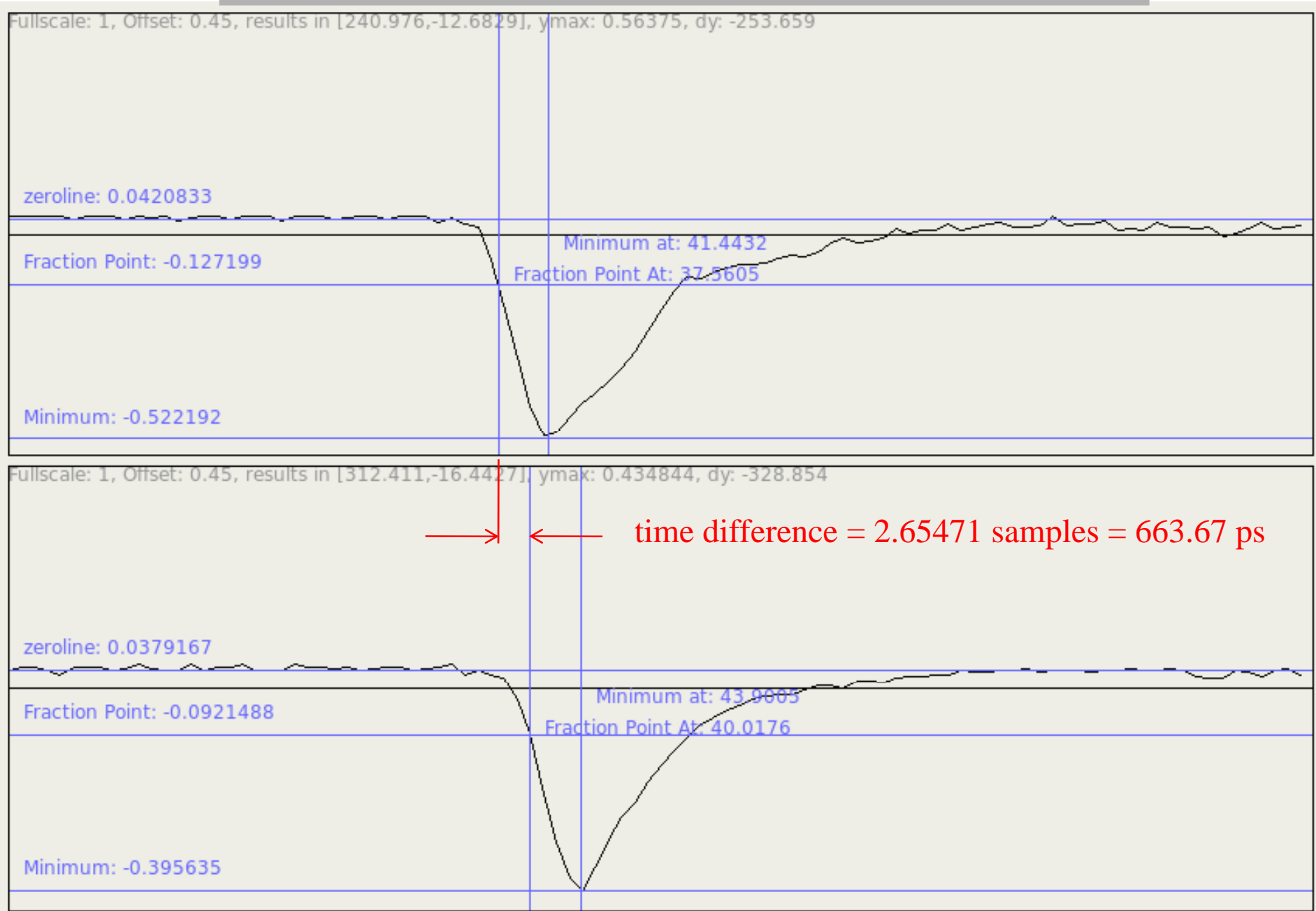
Positron lifetime: time between 1.27 MeV and 0.511 MeV quanta

Digital lifetime measurement

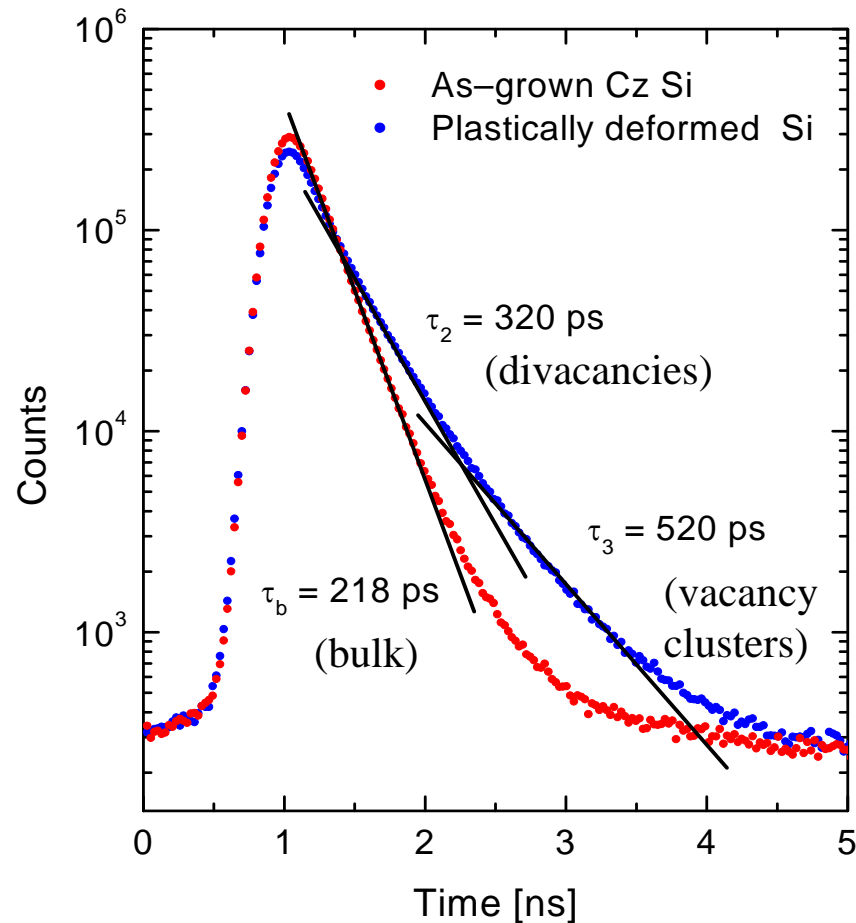


- much simpler setup
- timing very accurate ($<10^{-6}$ instead of 5×10^{-3})
- pulse-shape discrimination (suppress "bad pulses"): better time resolution
- each detector for start & stop (double statistics)

Screenshot of two digitized anode pulses



Positron lifetime spectroscopy



- positron lifetime spectra consist of exponential decay components
- positron trapping in open-volume defects leads to long-lived components
- longer lifetime due to lower electron density
- analysis by non-linear fitting: lifetimes τ_i and intensities I_i

positron lifetime spectrum:

$$N(t) = \sum_{i=1}^{k+1} \frac{I_i}{\tau_i} \exp\left(-\frac{t}{\tau_i}\right)$$

trapping coefficient

$$k_d = \mu C_d = \frac{I_2}{I_1} \left(\frac{1}{\tau_b} - \frac{1}{\tau_d} \right)$$

trapping rate

defect concentration



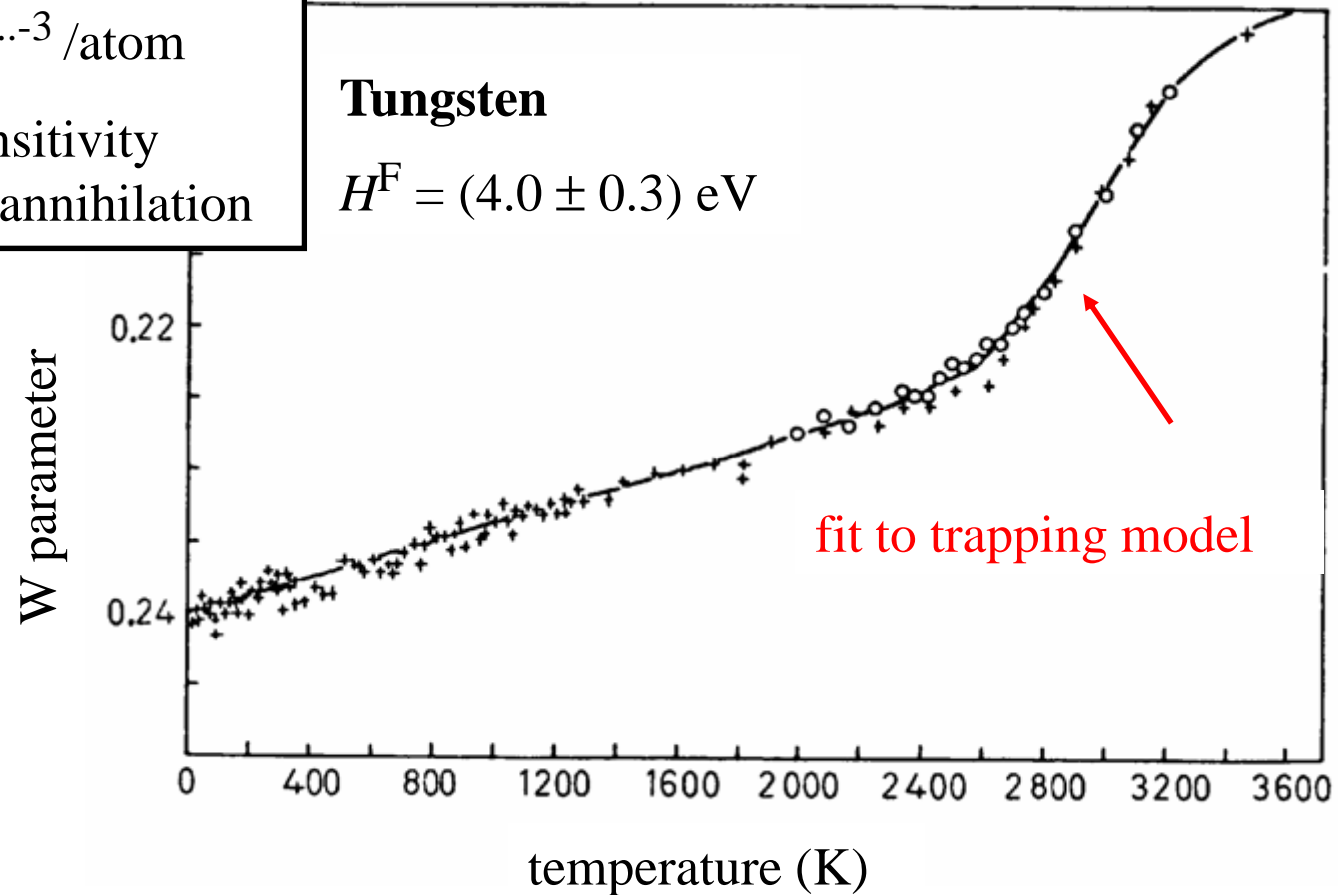
Vacancies in thermal Equilibrium

- Vacancy concentration in thermal equilibrium:
- in metals $H^F \approx 1...4 \text{ eV} \Rightarrow$ at $T_m [1v] \approx 10^{-4...-3} / \text{atom}$
- fits well to the sensitivity range of positron annihilation

$$C_{1v}(T) = \exp\left(\frac{S_{1v}^F}{k}\right) \exp\left(\frac{H_{1v}^F}{kT}\right)$$

Tungsten

$$H^F = (4.0 \pm 0.3) \text{ eV}$$



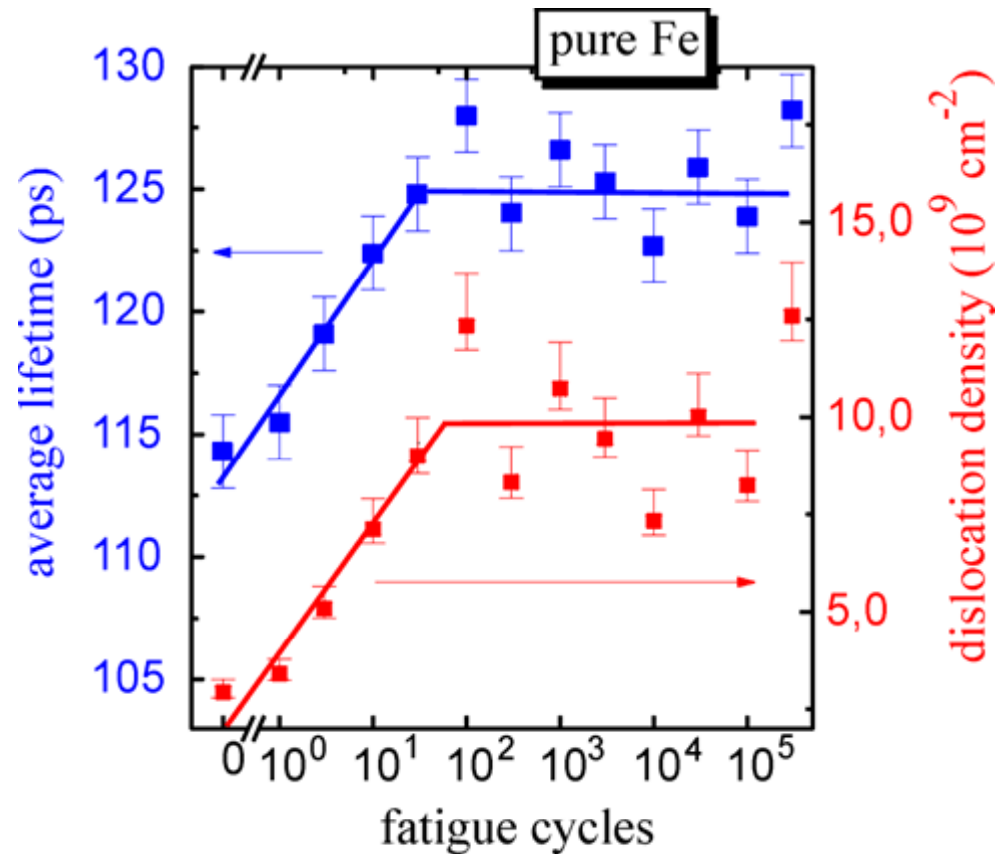
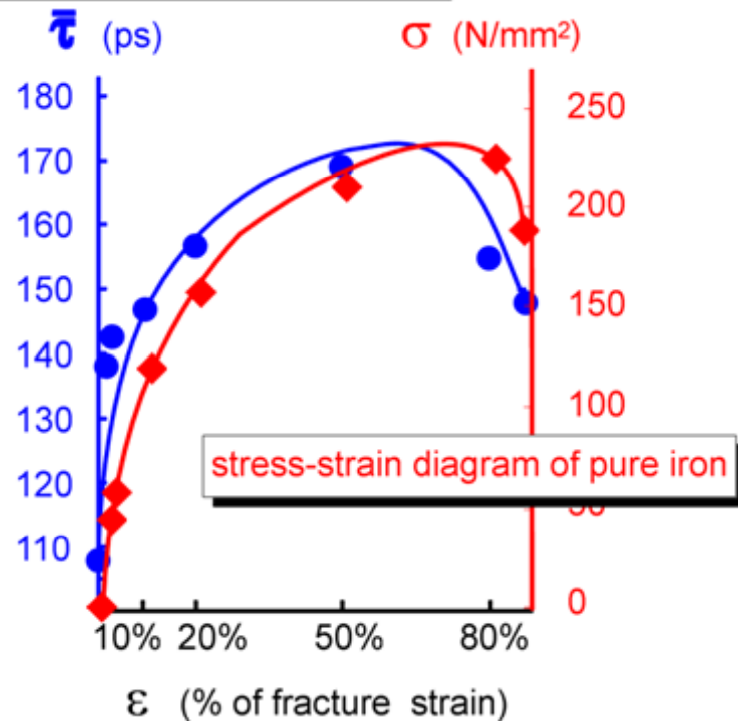
(Ziegler, 1979)



Defects in Iron after tensile strength and fatigue treatment

- We performed an extensive study of defects in mechanically damaged iron and steel
- Positrons are very sensitive: detection of defects already in the Hooks range of the stress-strain experiment
- Vacancy cluster and dislocations are detectable in both cases

average positron lifetime in pure iron after tensile strain

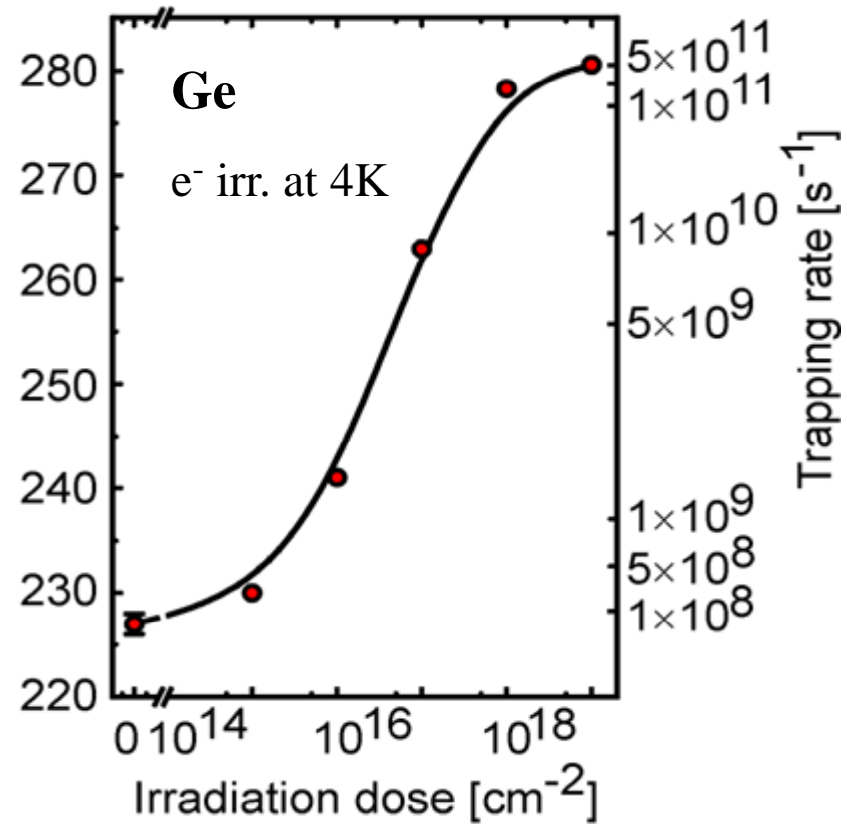
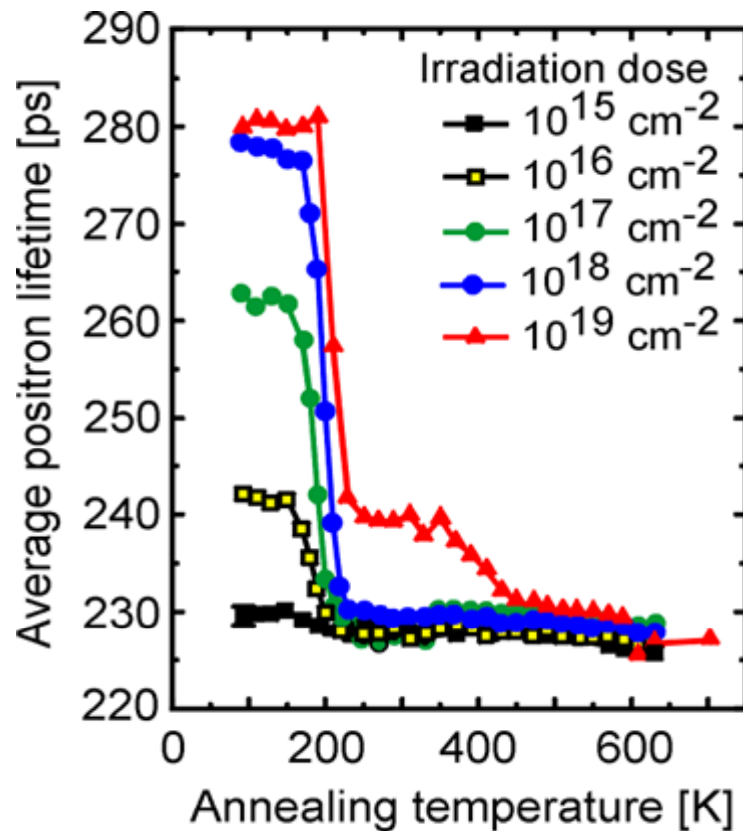


Somieski et al., J. Physique IV 5, C1/127-134 (1995)



Defects in electron-irradiated Ge

- Electron irradiation (2 MeV @ 4K) induces Frenkel pairs (vacancy - interstitial pairs)
- steep annealing stage at 200 K
- at high irradiation dose: divacancies are formed (thermally more stable)

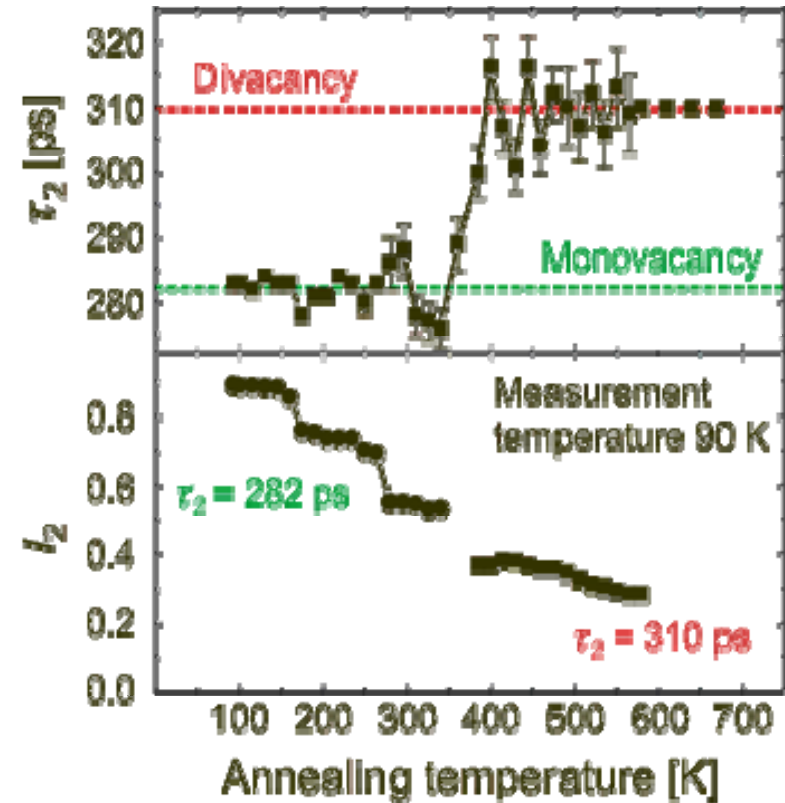
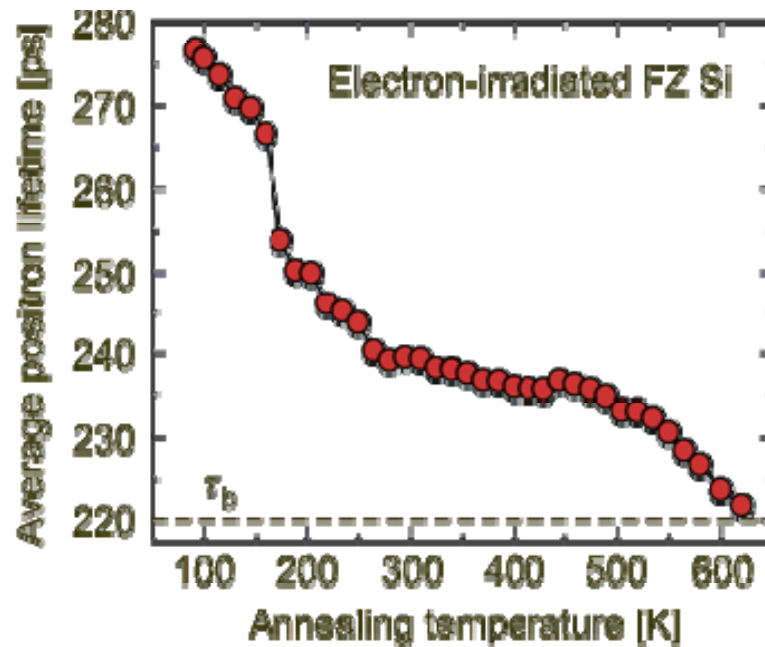


(Polity et al., 1997)



Electron irradiation of Si

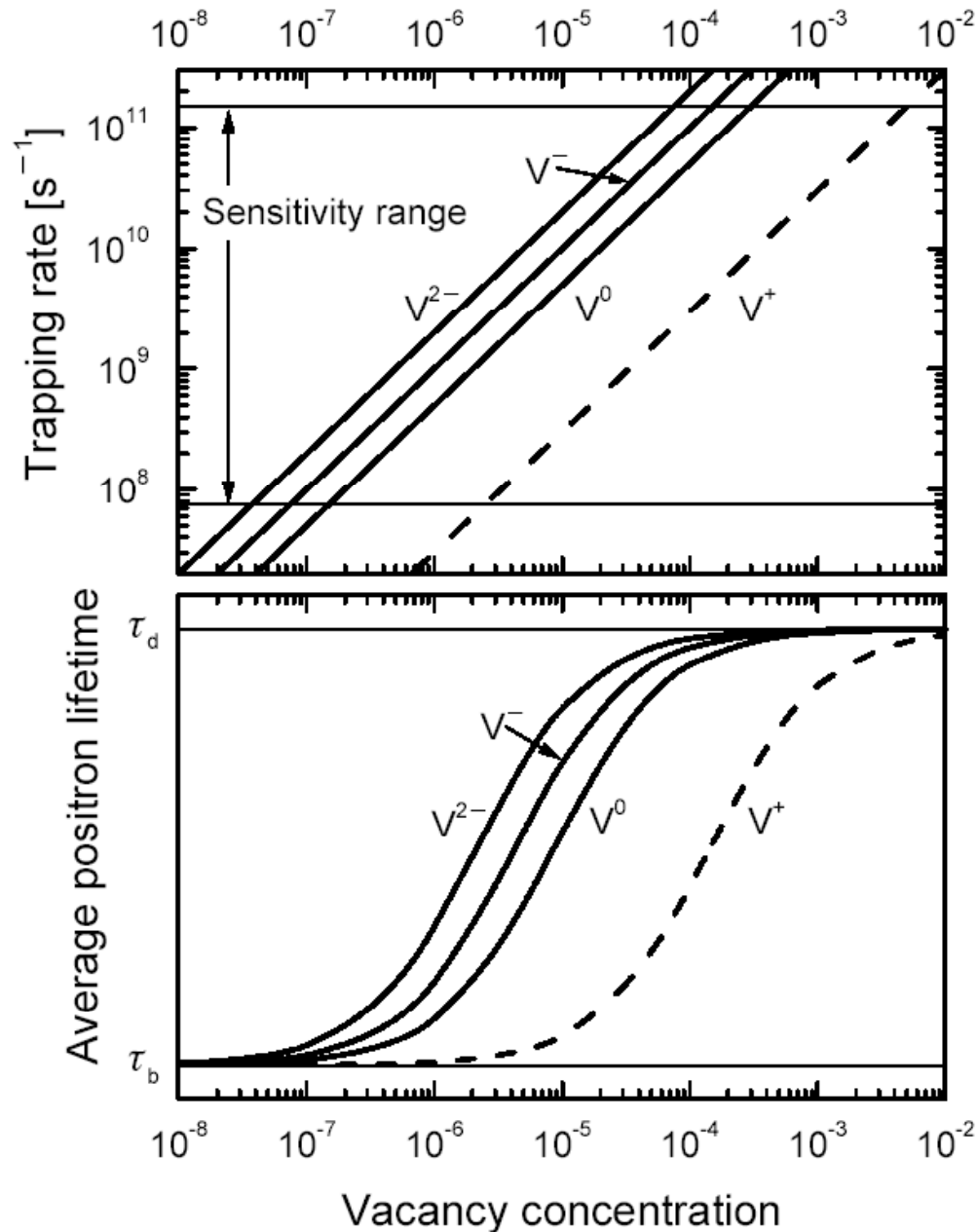
- low-temperature electron irradiation was performed at 4K ($E_e = 2$ MeV)
- annealing stage of monovacancies at about 170 K
- moving V_{Si} partly form divacancies
- divacancies anneal at about 550...650 K



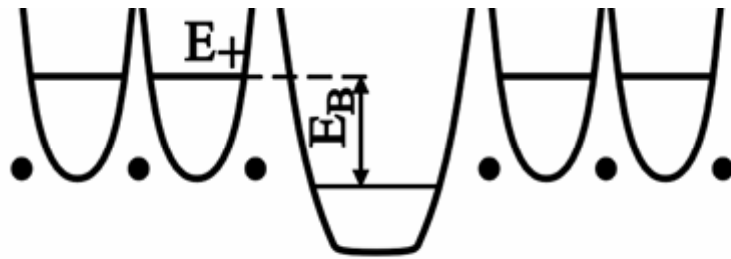
Polity et al., Phys. Rev. B **58** (1998) 10363



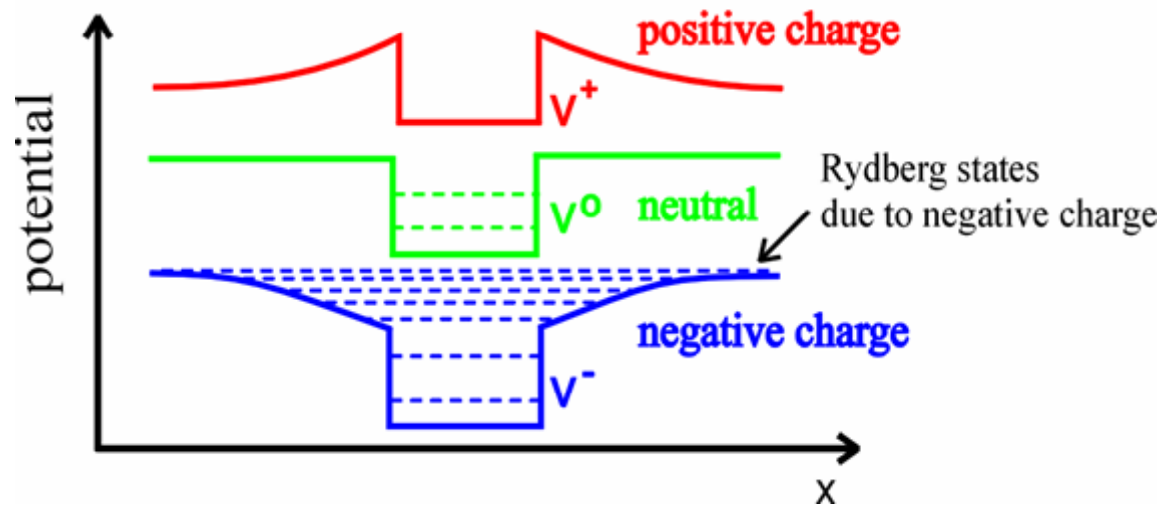
Sensitivity limits of PAS for vacancy detection



- **lower sensitivity limit** e.g. for negatively charged divacancies in Si starts at about 10^{15} cm^{-3}
- **upper limit**: saturated positron trapping
- defect identification still possible
- Then: only lower limit for defect density can be given



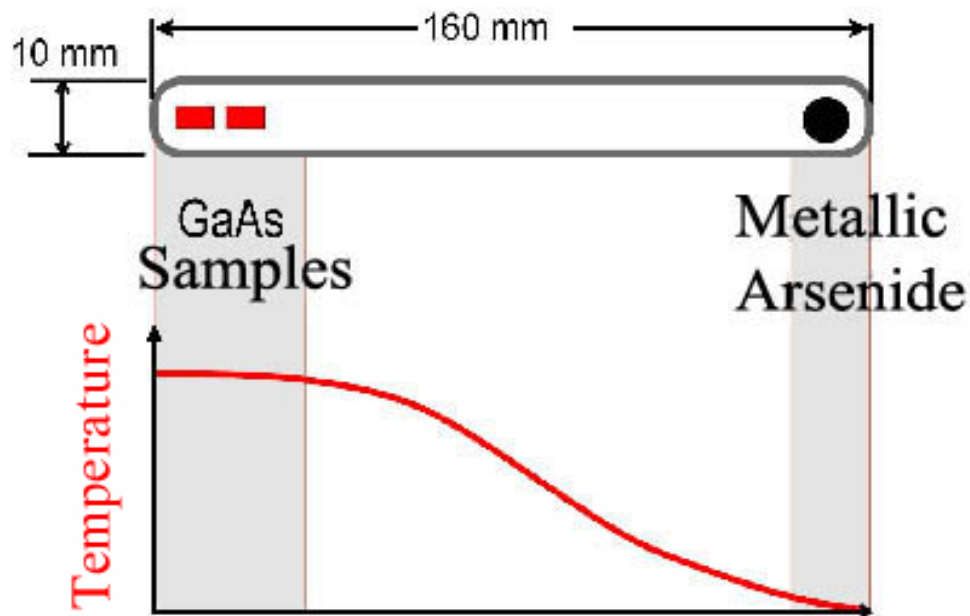
Vacancies in a semiconductor may be charged



- in a metal: charge of a vacancy is effectively screened by free electrons
- they are not available in semiconductors
- thus, long-range Coulomb potential added
- positrons may be attracted or repelled
- trapping coefficient μ is function of charge state

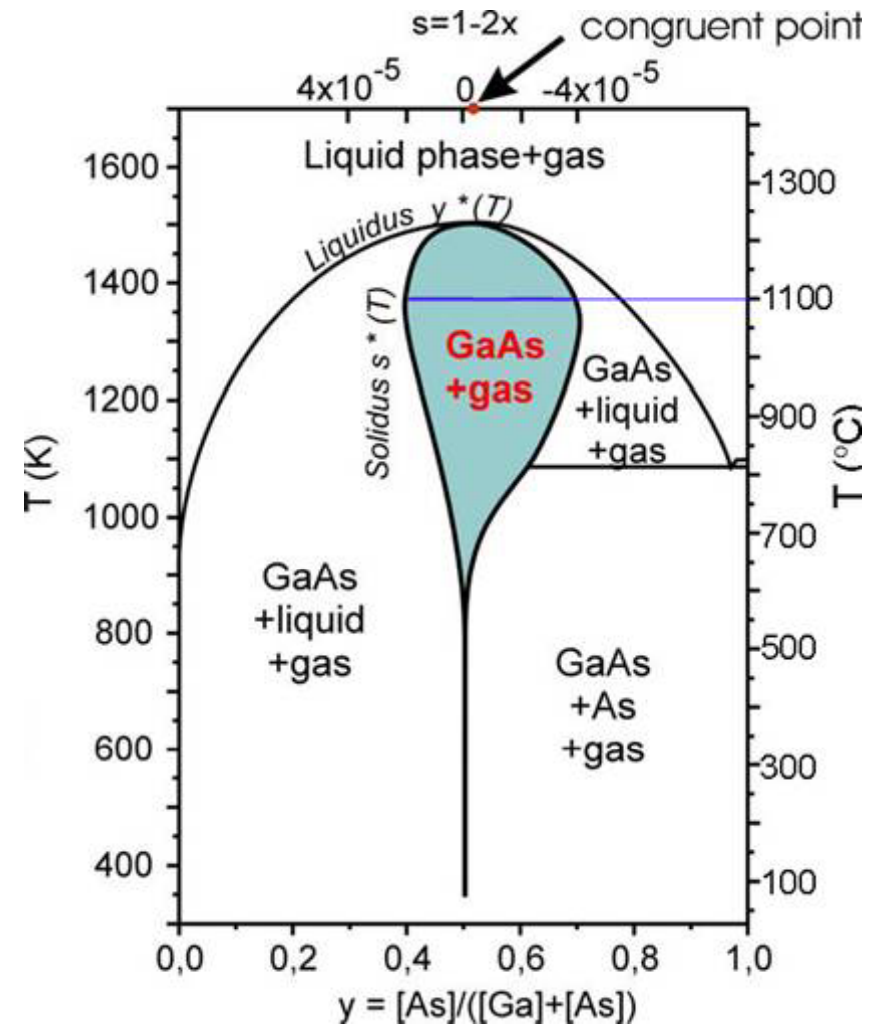
GaAs: annealing under defined As-partial pressure

- two-zone-furnace: Control of sample temperature **and** As partial pressure allows to navigate freely in phase diagram (existence area of compound)



$T_{\text{sample}}: 1100^{\circ} \text{C}$

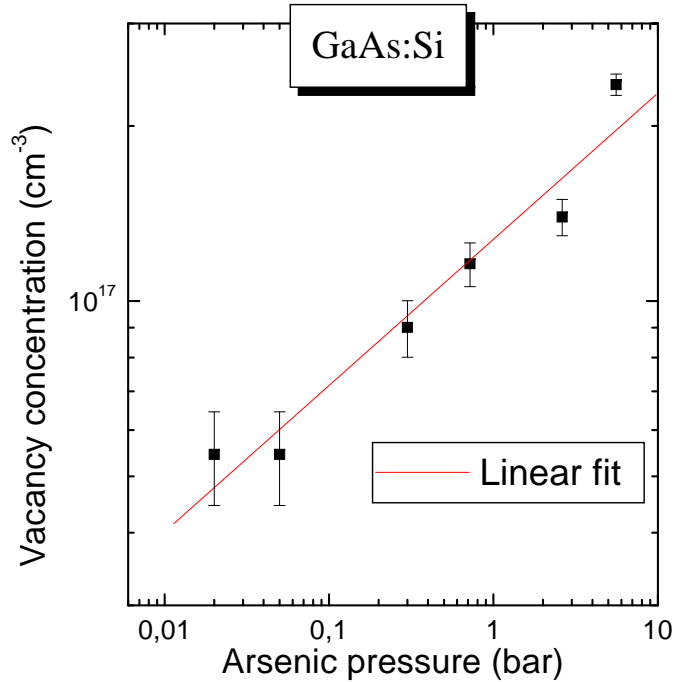
T_{As} : determines As-partial pressure



H. Wenzl et al., J. Cryst. Growth **109**, 191 (1991).

GaAs: Annealing under defined As pressure

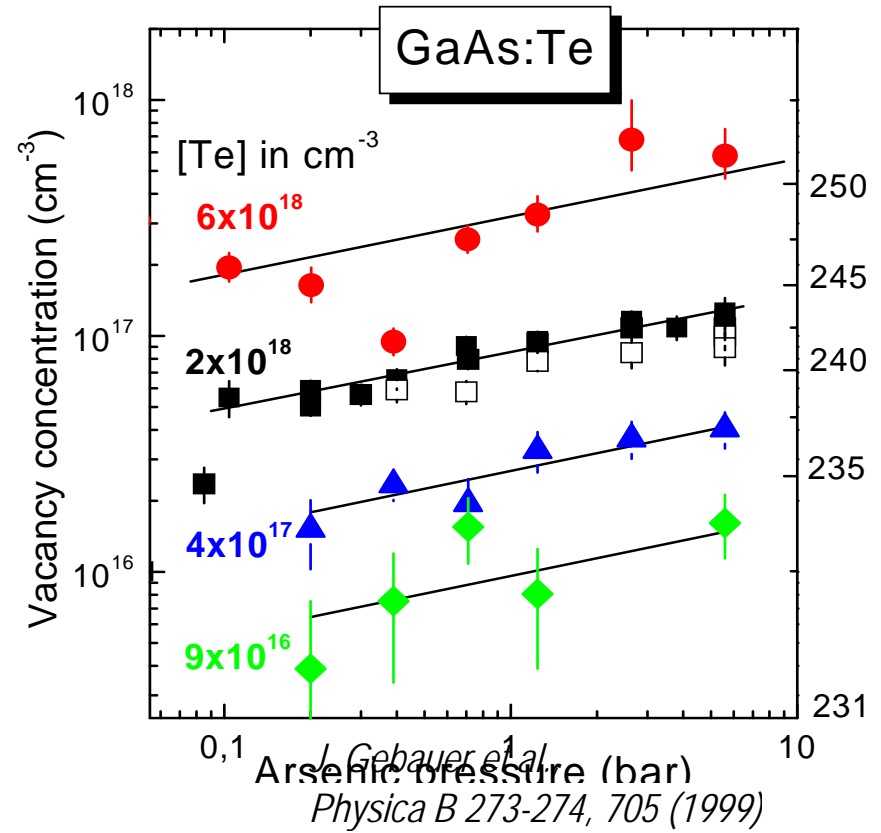
Si_{Ga}-V_{Ga}



Thermodynamic reaction:
 $1/4 \text{As}_4^{\text{gas}} \leftrightarrow \text{As}_{\text{As}} + \text{V}_{\text{Ga}}$

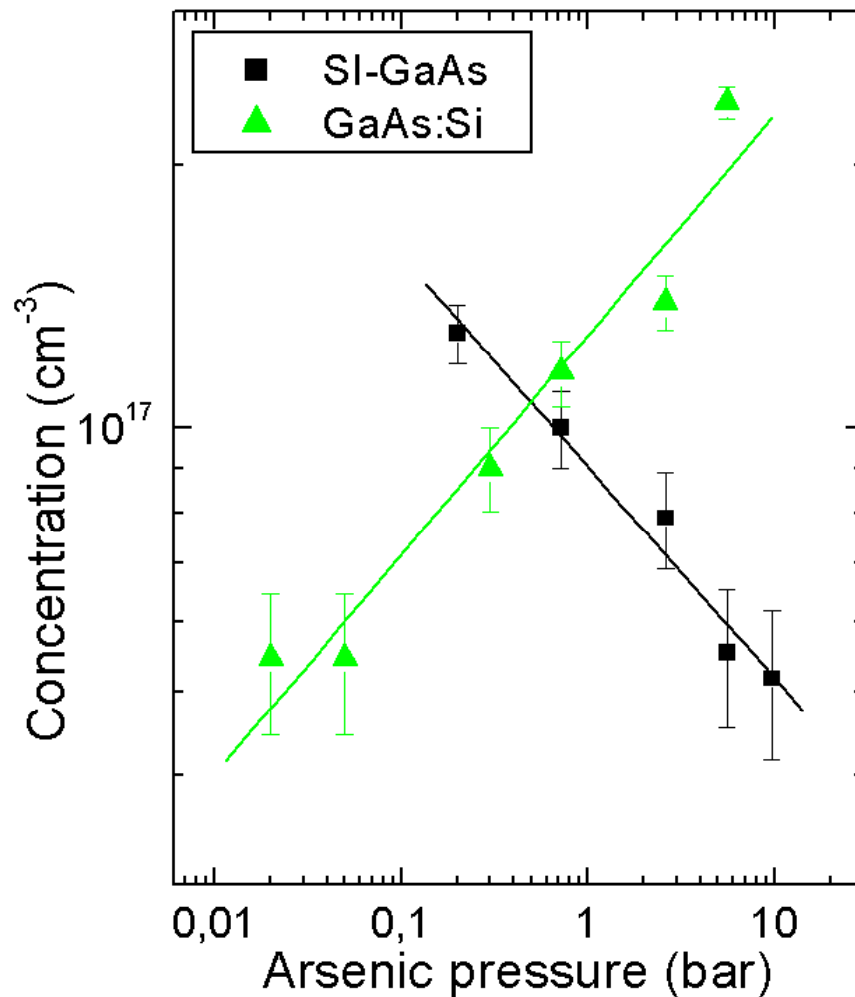
Mass action law:
 $[\text{V}_{\text{Ga}}] = K_{\text{VG}} \times p_{\text{As}}^{1/4}$

Te_{As}-V_{Ga}



Fit: $[\text{V}_{\text{Ga}}\text{-Dopant}] \sim p_{\text{As}}^n$
→ $n = 1/4$

Comparison of doped and undoped GaAs



Bondarenko et al., 2003

Thermodynamic reaction:



Mass action law:

$$[\text{V}_{\text{As}}] = K_{\text{VAs}} \times p_{\text{As}}^{-1/4}$$

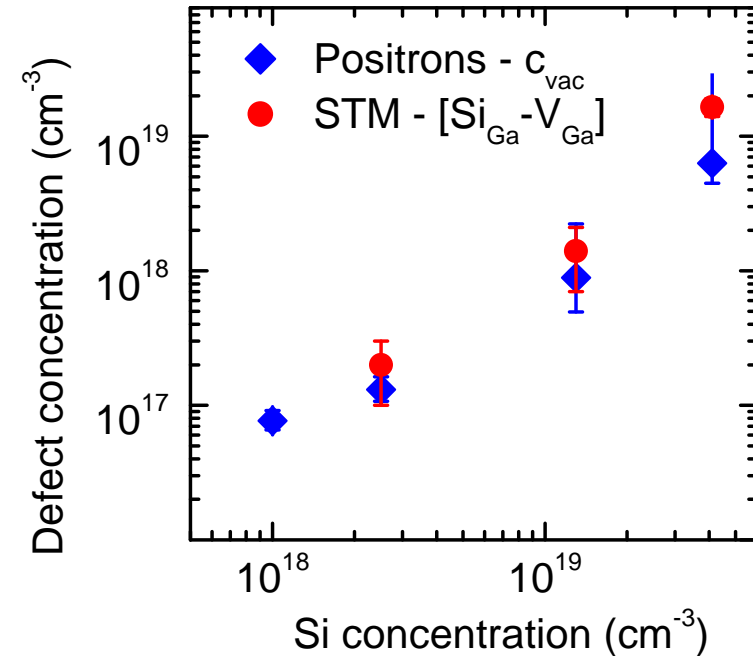
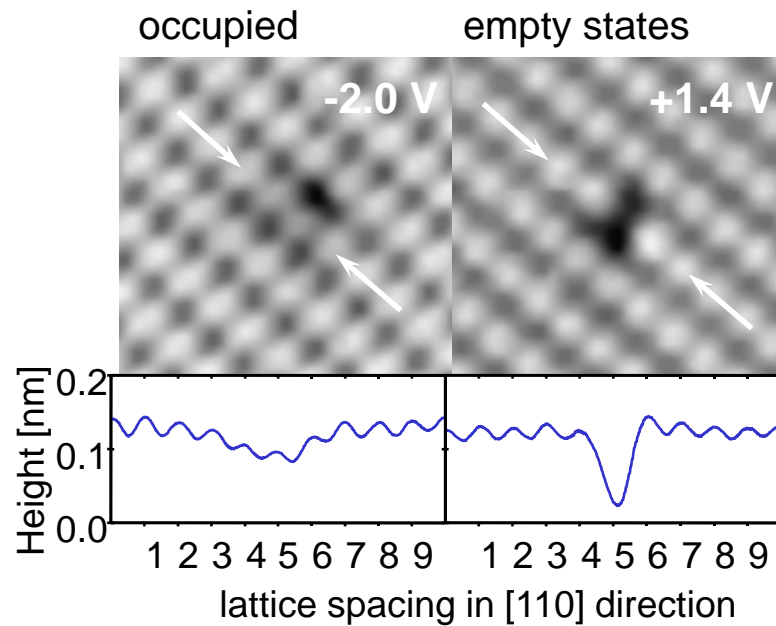
Fit: $[\text{V-complex}] \sim p_{\text{As}}^n$

$$\rightarrow n = -1/4$$

undoped GaAs: As vacancy



Identification of V_{Ga} - Si_{Ga} -Complexes in GaAs:Si



- Scanning tunneling microscopy at GaAs (110)-cleavages planes (by Ph. Ebert, Jülich)
- Defect complex identified as V_{Ga} - Si_{Ga}

- Quantification → Agreement

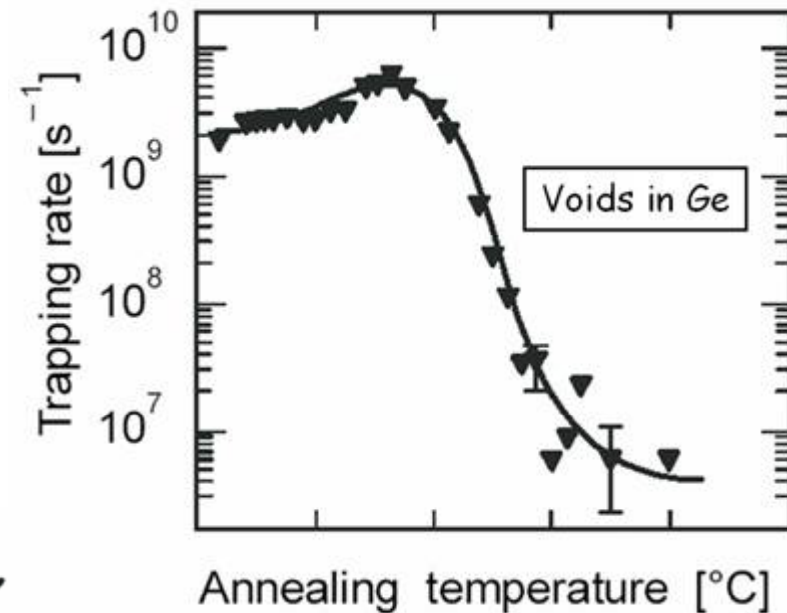
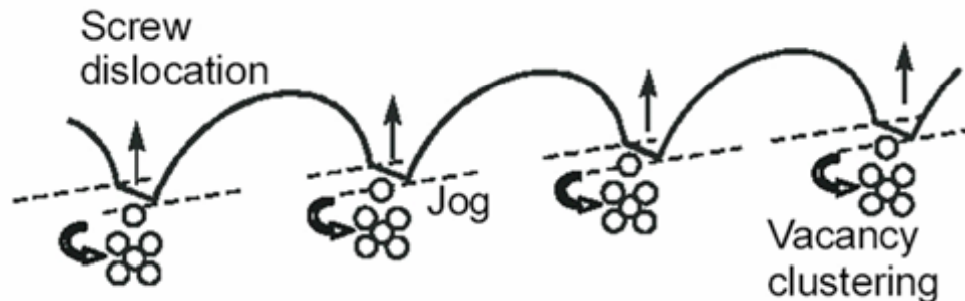
Mono-Vacancies in GaAs:Si are V_{Ga} - Si_{Ga} -complexes

Gebauer et al., Phys. Rev. Lett. **78** (1997) 3334



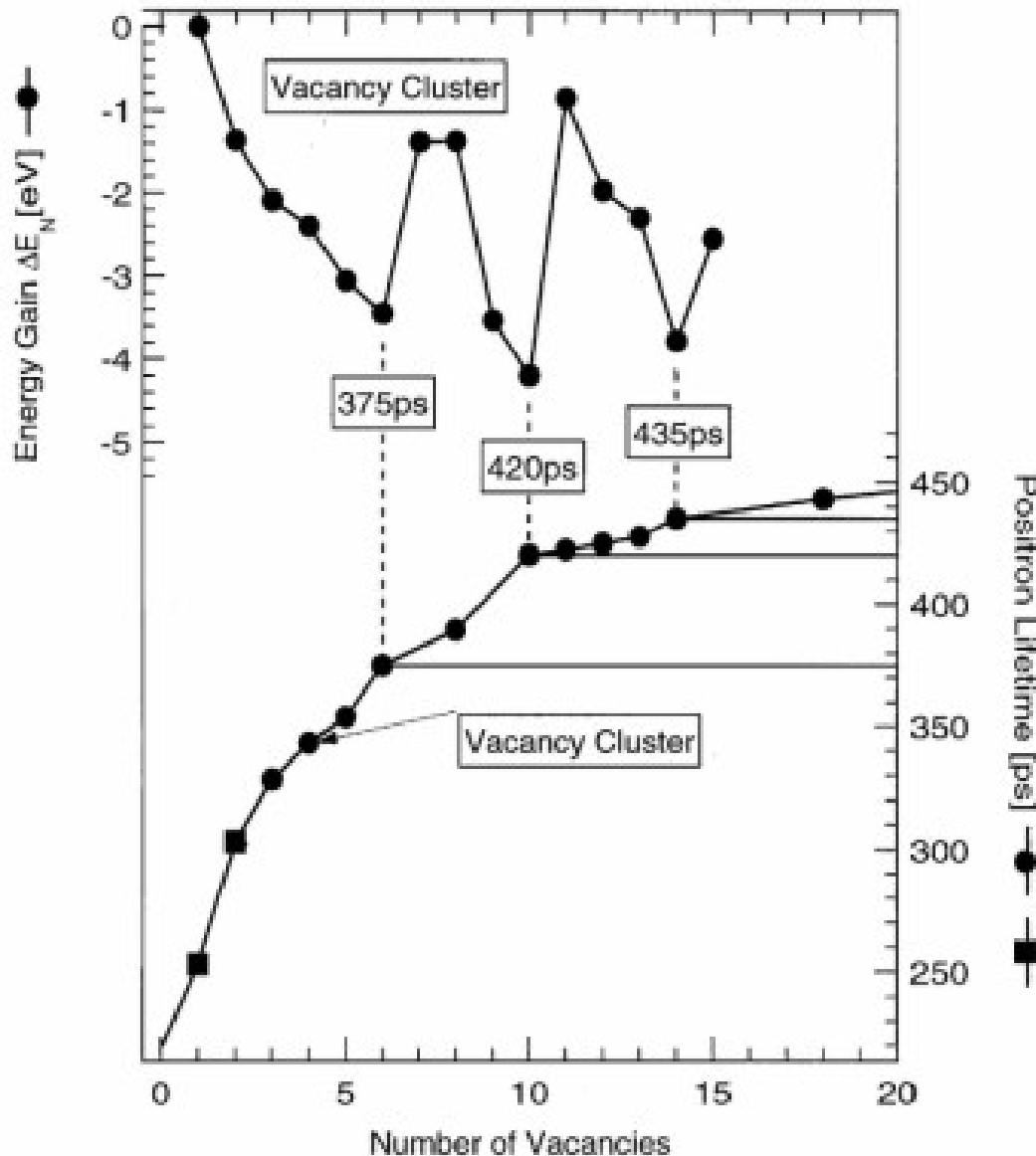
Vacancy clusters in semiconductors

- vacancy clusters were observed after neutron irradiation, ion implantation and plastic deformation
- due to large open volume (low electron density) -> positron lifetime increases distinctly
- example: plastically deformed Ge
- defect lifetime: $\tau = 525$ ps
- reason for void formation: jog dragging mechanism
- trapping rate of voids disappears during annealing experiment



Krause-Rehberg et al., 1993

Theoretical calculation of vacancy clusters in Si

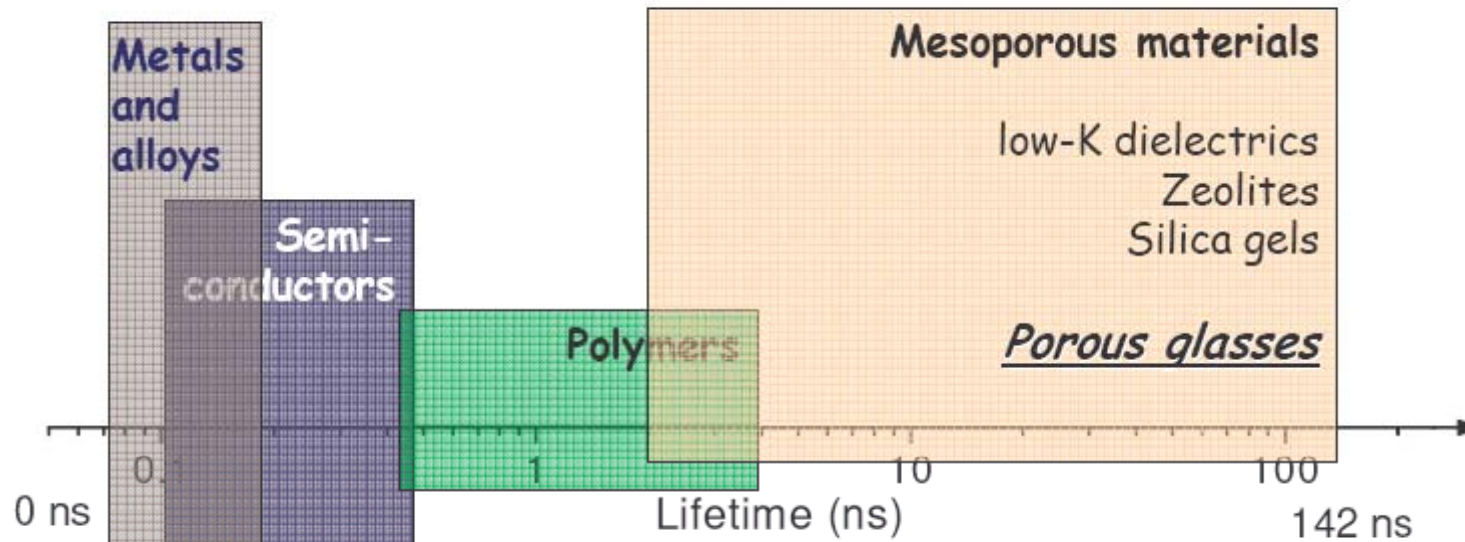


- there are cluster configurations with a large energy gain
- „Magic Numbers“ with 6, 10 und 14 vacancies
- positron lifetime increases distinctly with cluster size
- for $n > 10$ saturation effect, i.e. size cannot be determined

T.E.M. Staab et al.,
Physica B 273-274 (1999) 501-504



Typical Lifetimes



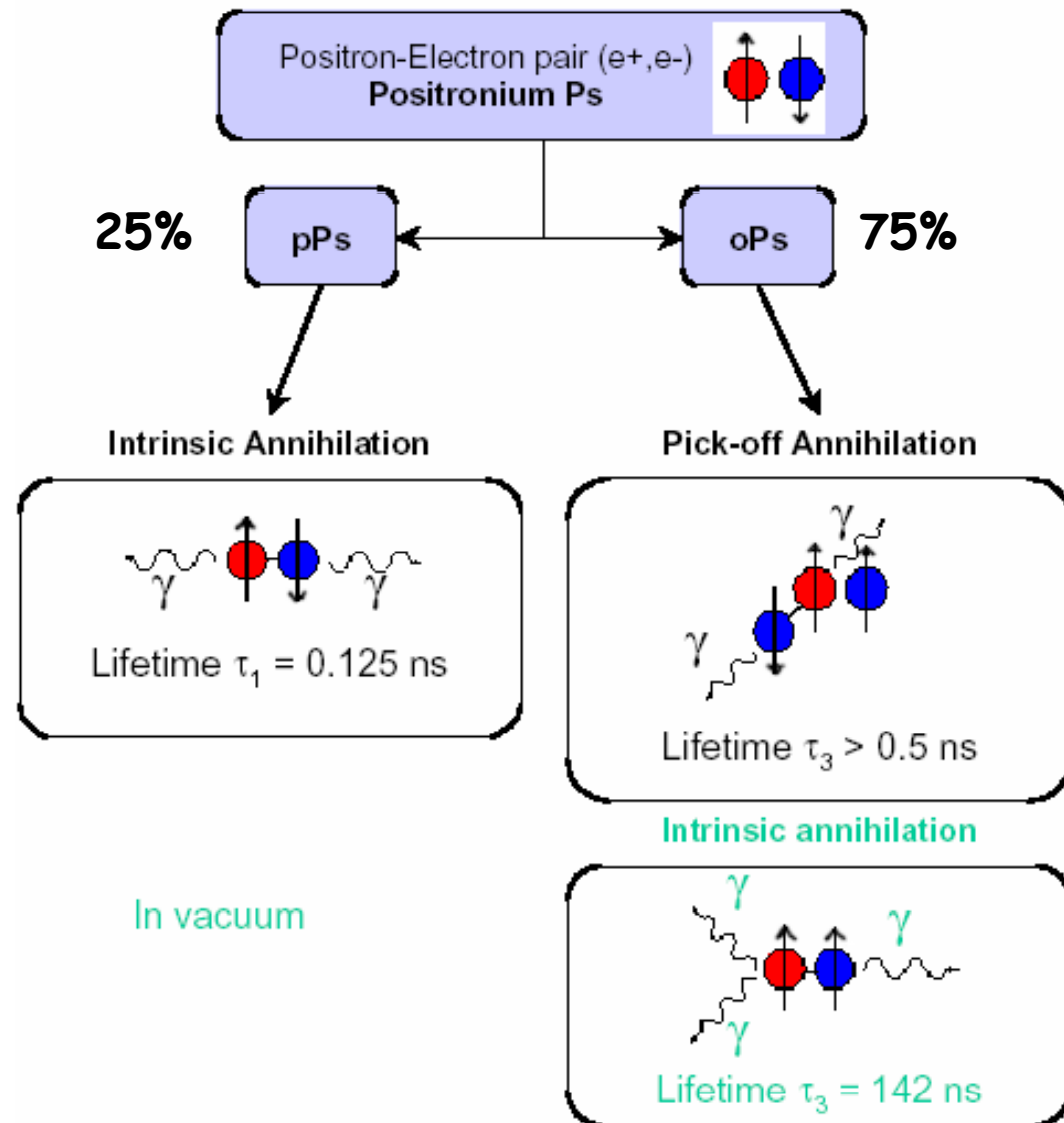
Positron

Positronium



Principles of PALS: ortho-Positronium

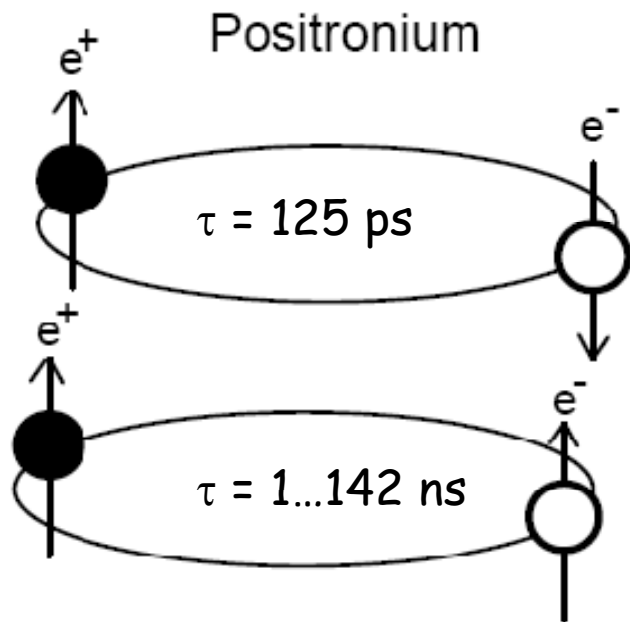
In materials without free electrons Positronium may be formed (Polymers, glass, liquids, gases).



Pick-off annihilation

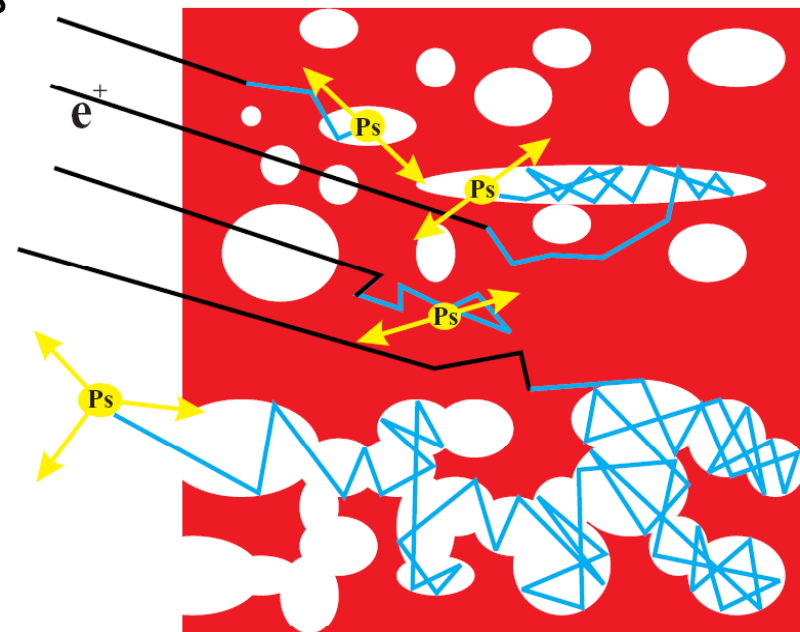
pick-off annihilation:

- o-Ps is converted to p-Ps by capturing an electron with anti-parallel spin
- happens during collisions at walls of pore
- lifetime decreases rapidly
- lifetime is function of pore size 1.5 ns to 142 ns

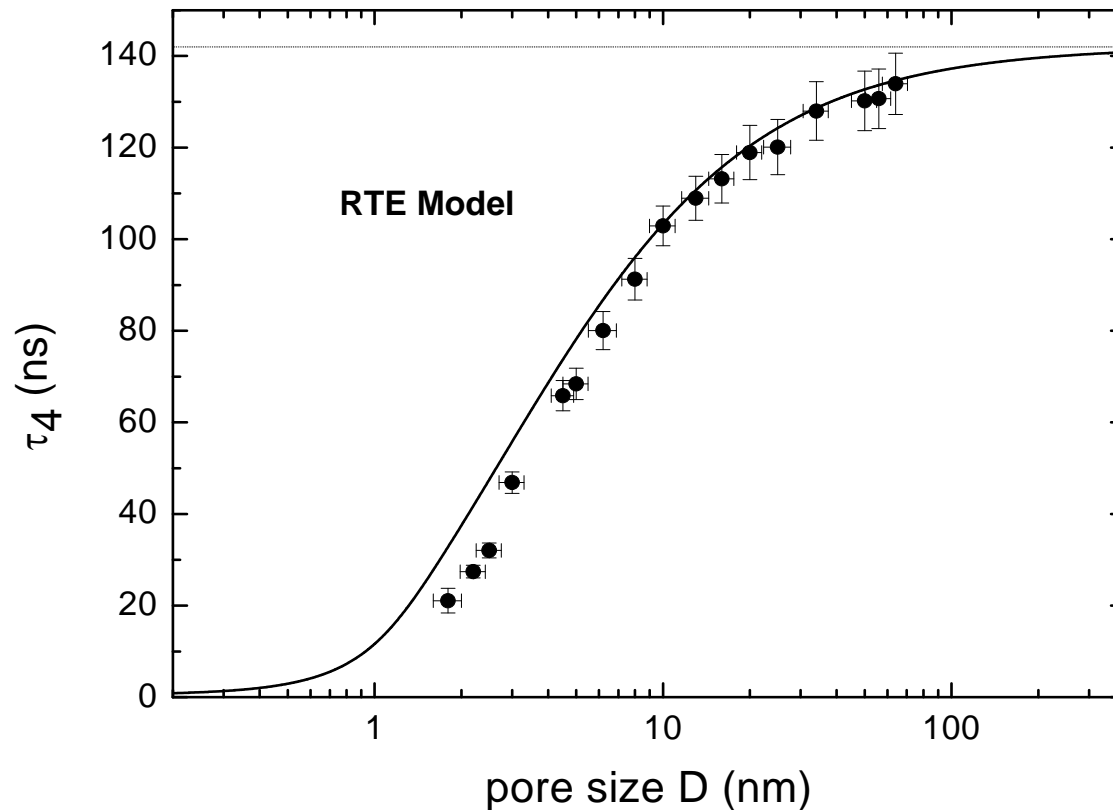


para-Ps
 1S_0

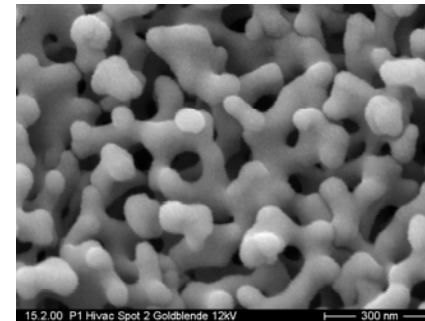
ortho-Ps
 3S_1



σ -Ps lifetime τ_4 versus pore size



- we measured porous CPG glass in a broad pore size range

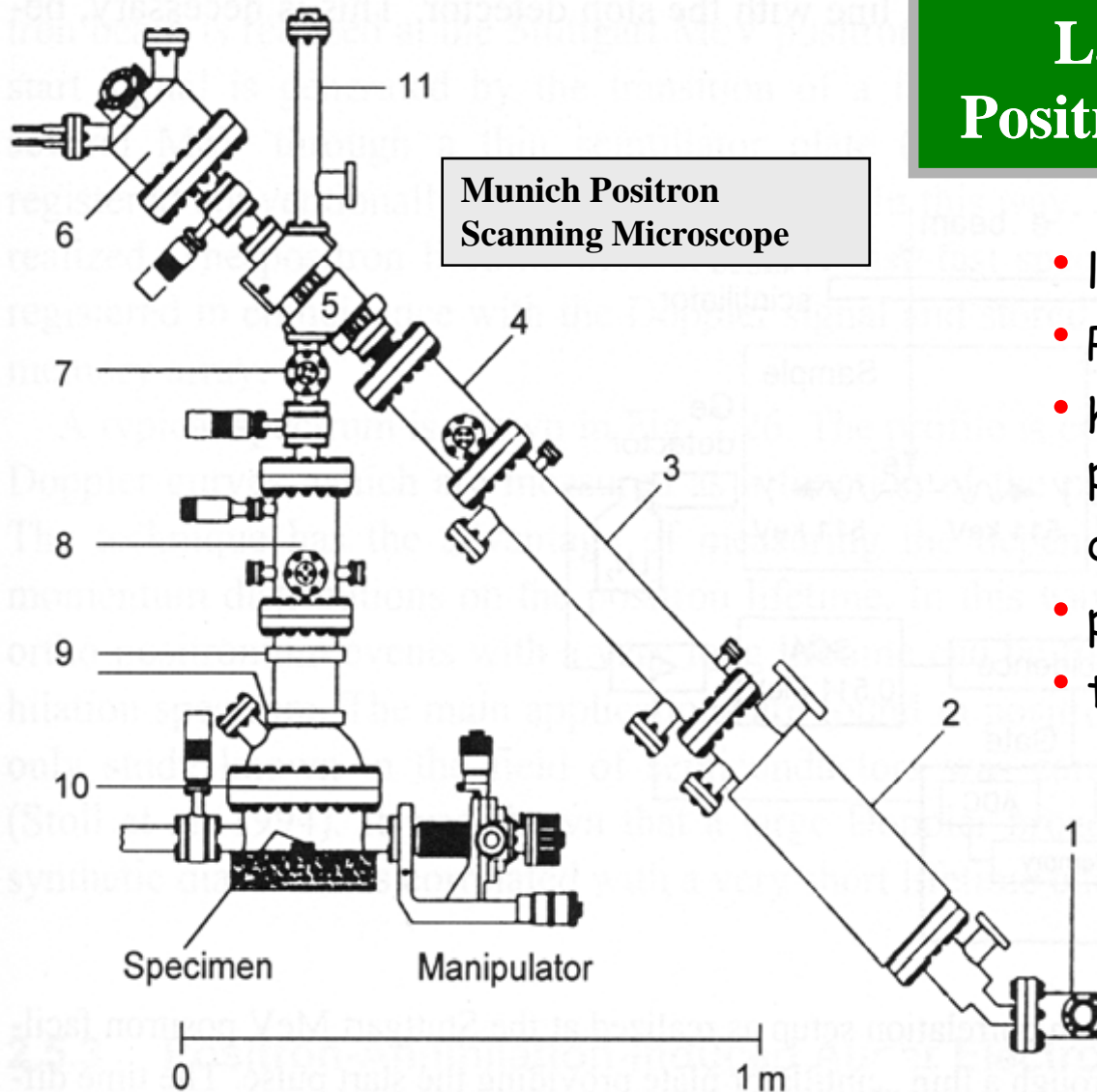


- given pore size obtained by N_2 -adsorption and/or mercury intrusion technique
- for $T=300$ K fair agreement to the RTE model for large pores

RTE model: D. W. Gidley, T. L. Dull, W. E. Frieze, J. N. Sun, A. F. Yee, *J. Phys. Chem. B* **2001**, *105*, 4657.



Lateral Resolution with Positron-Scanning-Microscope

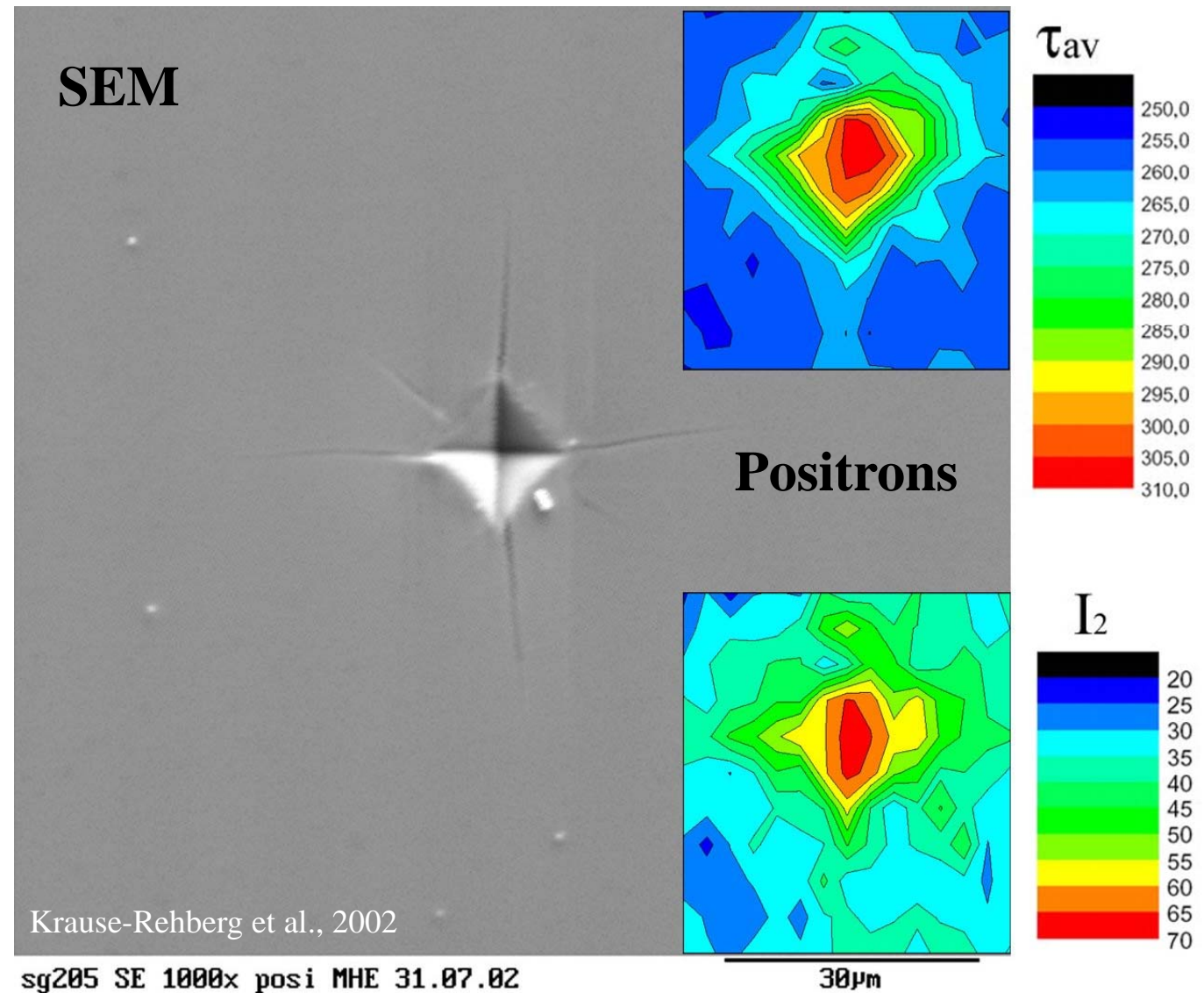


- lateral resolution $2 \mu\text{m}$
- Positron lifetime spectroscopy
- however lateral resolution principally limited by positron diffusion ($L_+ \approx 100\text{nm}$)
- problem: low count rate
- transfer to FRM-II

W. Triftshäuser et al., NIM B **130** (1997) 265

Microhardness indentation in GaAs

- Comparison of SEM and Munich Positron Scanning Microscope
- problem here at the moment: intensity
- hope: strong positron source at FRM-II Garching or EPOS project in Rossendorf

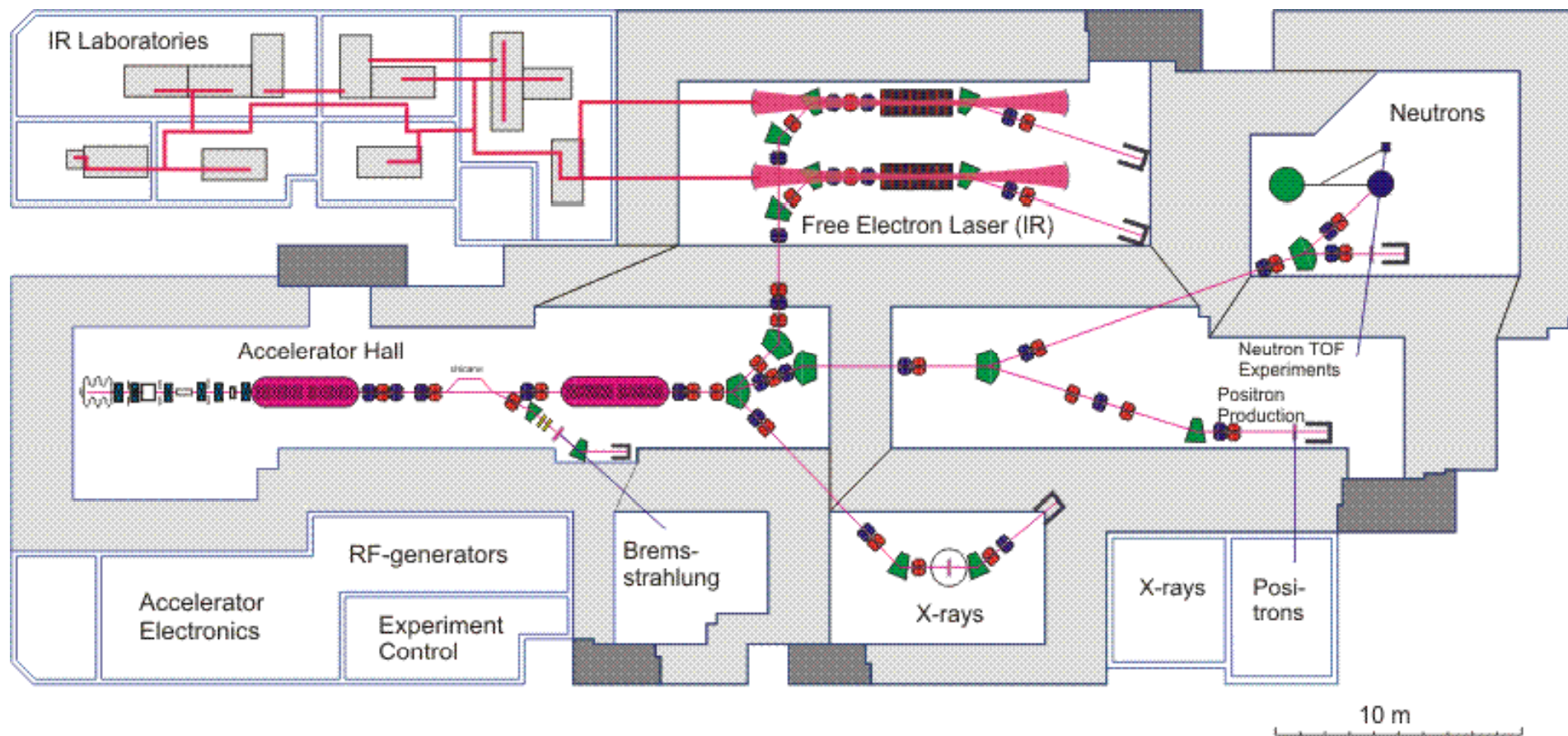


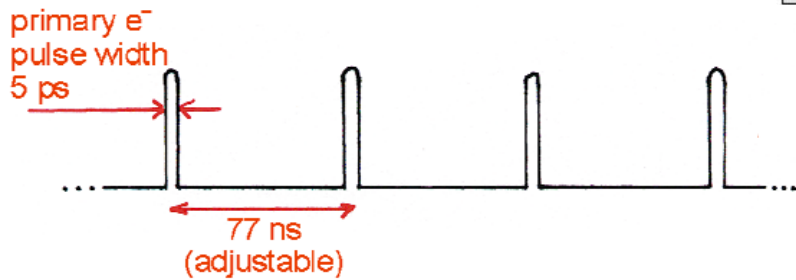
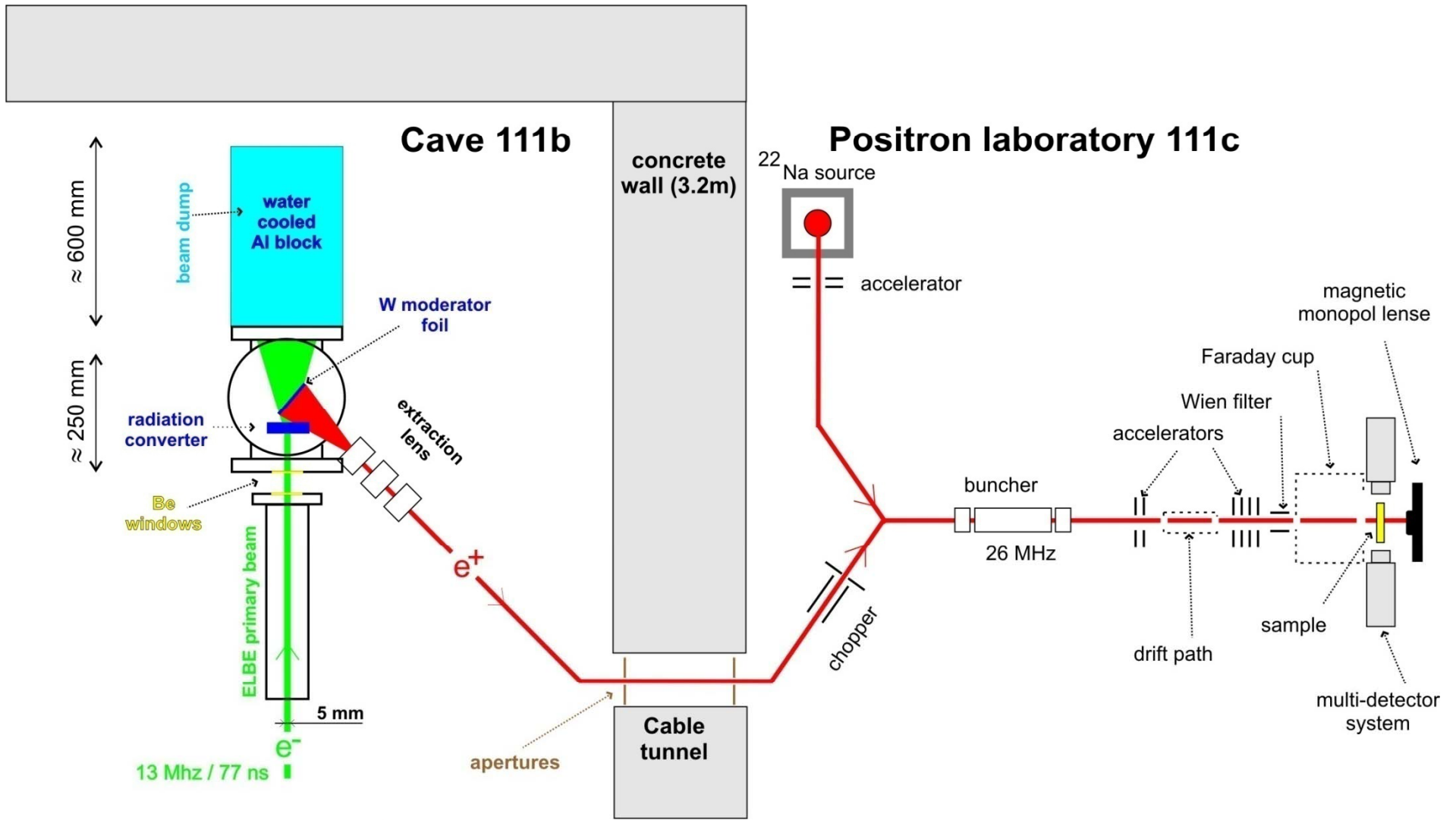
EPOS = ELBE Positron Source

- ELBE -> electron LINAC (40 MeV and up to 40 kW) in Research Center Dresden-Rossendorf
- EPOS will be the combination of a positron lifetime spectrometer, Doppler coincidence, and AMOC
- user-dedicated facility
- main features:
 - high-intensity bunched positron beam ($E_+ = 0.5...30$ keV)
 - very good time resolution by using the unique primary time structure of ELBE
 - high quality spectra by lifetime and Doppler spectroscopy in coincidence mode
 - very high count rate by multi-detector array
 - all spectrometers digital
 - conventional source included for Doppler measurements (when primary beam is not available)
 - fully remote control via internet by user



Ground plan of the ELBE hall





EPOS scheme

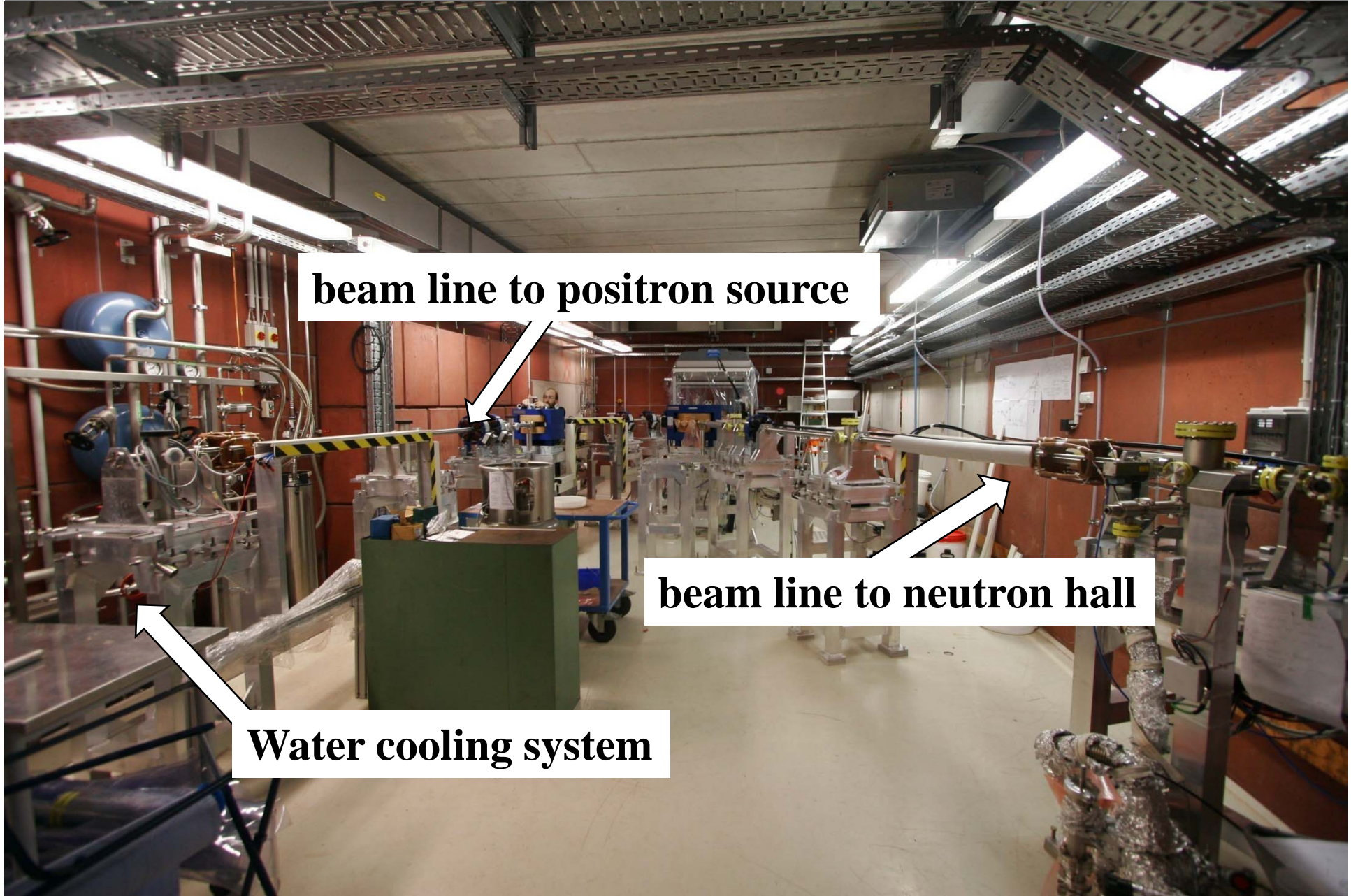


Cave 111b

beam line to positron source

beam line to neutron hall

Water cooling system



EPOS - Applications

Variety of applications in all field of materials science:

- defect-depth profiles due to surface modifications and ion implantation
- tribology (mechanical damage of surfaces)
- polymer physics (pores; interdiffusion; ...)
- low-k materials (thin high porous layers)
- defects in semiconductors, ceramics and metals
- epitaxial layers (growth defects, misfit defects at interface, ...)
- fast kinetics (e.g. precipitation processes in Al alloys; defect annealing; diffusion; ...)
- radiation resistance (e.g. space materials)
- many more ...



Conclusions

- Positrons are a unique tool
 - for characterization of vacancy-type defects in crystalline solids
 - for embedded nano-particles (e.g. small precipitates)
 - for nano-porosimetry
- New facilities become available for user-dedicated operation having
 - better time resolution and spectra quality
 - lateral resolution 1 μm
 - much higher intensity

This presentation can be found as pdf-file on our Website:
<http://positron.physik.uni-halle.de>

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